

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--------------------------------------------------------|--------------------------------------------|------------------|---------|---------------------|
| L1 | 20 | noda-takaaki.in. | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 14:42 |
| L2 | 7 | suzaki-kenichi.in. | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 14:42 |
| L3 | 4060 | (427/248.1,255.23,255.28,255.38,255.395).CCLS. | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | OFF | 2008/02/12 14:48 |
| L4 | 2987 | (438/478,758,800,900,909,932,935).CCLS. | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | OFF | 2008/02/12 14:52 |
| L5 | 5 | (L1 L2) and purge and (silicon monosilane) and (boron) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 14:55 |
| L6 | 160 | (L3 L4) and purge and (silicon monosilane) and (boron) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 14:55 |
| L7 | 2 | ("6171104").PN. | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | OFF | 2008/02/12 14:57 |

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|-----|-----|-----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|--------------------------------------------|----|----|---------------------|
| L8 | 8 | ((L3 L4) and ((purge with (inert adj gas)) same (chamber furnace reactor)) and (silicon monosilane) and ((doped doping) with boron) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 15:03 |
| L9 | 97 | ((purge with (inert adj gas)) same (chamber furnace reactor)) and (silicon monosilane) and ((doped doping) with boron) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 15:03 |
| L10 | 289 | ((purge with (inert adj gas)) same (chamber furnace reactor)) and (silicon monosilane) and (boron) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 15:06 |
| L11 | 235 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 15:59 |
| L12 | 12 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") same purg\$3 | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:00 |
| L13 | 0 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with clean\$3 with (chamber reactor furnace)) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:14 |
| L14 | 8 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with (clean\$3 evacuat\$3) with (chamber reactor furnace)) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:15 |
| L15 | 21 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with (clean\$3 evacuat\$3)) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:16 |
| L16 | 3 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with (clean\$3)) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:16 |

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|-----|----|-----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|--------------------------------------------|----|----|---------------------|
| L17 | 18 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with remov\$3 with (substrate wafer))) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:19 |
| L18 | 0 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with (remov\$3 near2 (substrate wafer))) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:20 |
| L19 | 67 | (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with (remov\$3 near2 (substrate wafer))) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:20 |
| L20 | 47 | (silane silicon) same (boron "bcl.sub.3") and (purg\$3 with (remov\$3 near1 (substrate wafer))) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:23 |
| L21 | 7 | ("20030053893" "20030077150" "5540098" "6066210" "6143083" "6573178").PN. OR ("6720274").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2008/02/12 16:29 |
| L22 | 3 | ("20030180556" "6323139" "6468903").PN. OR ("6790793").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2008/02/12 16:29 |
| L23 | 3 | ("5637153" "5963834").PN. OR ("6573178").URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2008/02/12 16:32 |
| L24 | 2 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane monosilane) same ((boron adj trichloride) "bcl.sub.3") | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:44 |
| L25 | 7 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) same (silane silicon "sih. sub.4" monosilane) same ((boron adj trichloride) "bcl.sub.3") | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:46 |
| L26 | 25 | (ald (atomic adj layer adj deposit\$3) (cyclic adj deposit\$3) (atomic adj layer adj epitaxy)) and ((silane monosilane) same ((boron adj trichloride) "bcl.sub.3")) | US-PGPUB; USPAT; DERWENT; IBM_TDB | OR | ON | 2008/02/12 16:50 |

2/ 12/ 2008 4:53:13 PM

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